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(71)Applicant : FUJI PHOTO FILM CO LTD

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(54) POSITIVE CHEMICALLY AMPLIFYING RESIST COMPOSITION

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a positive chemically amplifying resist composition having high sensitivity and high resolution which can give a square and superior pattern profile and which is excellent in PCD(post coating delay) and PED(post exposure delay) stability and coating property.

SOLUTION: The positive chemically amplifying resist composition contains a compound (a) which directly or indirectly produces radicals (A) by irradiation of energy rays.

LEGAL STATUS

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